

ESE370: Circuit-Level Modeling, Design, and Optimization for Digital Systems

Lec 8: September 22, 2021
MOS Transistor Operating Regions
Part 2



Today

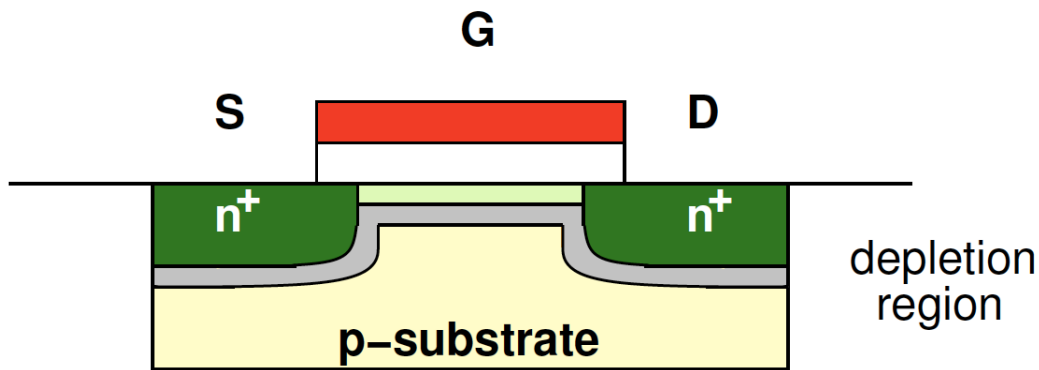
- Operating Regions (continued)
 - Resistive
 - Saturation
 - Subthreshold
 - Velocity Saturation
- Short Channel Effects
 - V_{th}
 - Drain Induced Barrier Lowering

Last Time...

Above Threshold

Linear Region

- $V_{GS} > V_{th}$ and V_{DS} small



$$C_{OX} = \frac{\epsilon_{OX}}{t_{OX}}$$

$$I_{DS} = \mu_n C_{OX} \left(\frac{W}{L} \right) \left[(V_{GS} - V_{th}) V_{DS} - \frac{V_{DS}^2}{2} \right]$$

Saturation

- In saturation, $V_{DS\text{-effective}} = V_x = V_{GS} - V_T$

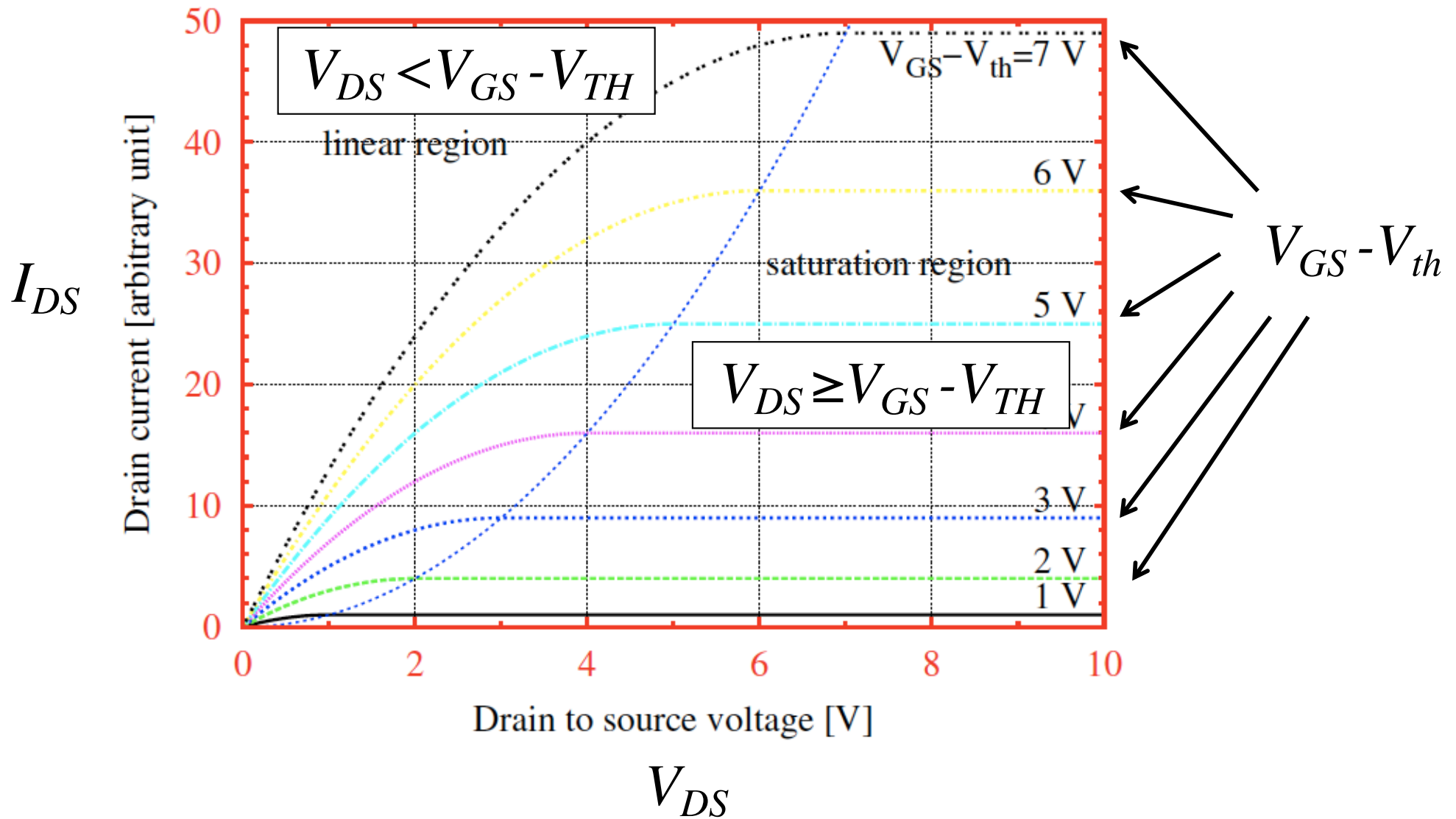
$$I_{DS} = \mu_n C_{OX} \left(\frac{W}{L} \right) \left[(V_{GS} - V_T) V_{DS} - \frac{V_{DS}^2}{2} \right]$$

- Becomes:

$$I_{DS} = \mu_n C_{OX} \left(\frac{W}{L} \right) \left[(V_{GS} - V_T)^2 - \frac{(V_{GS} - V_T)^2}{2} \right]$$

$$I_{DS} = \frac{\mu_n C_{OX}}{2} \left(\frac{W}{L} \right) \left[(V_{GS} - V_T)^2 \right]$$

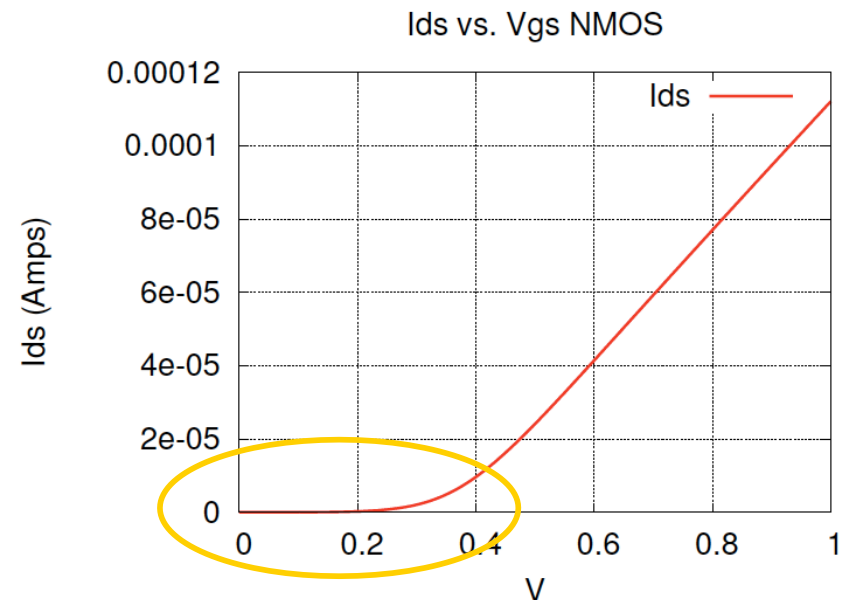
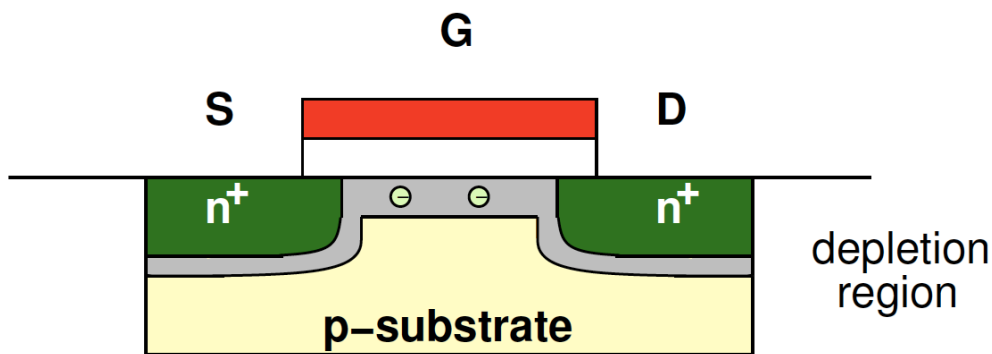
MOSFET – IV Characteristics



Subthreshold

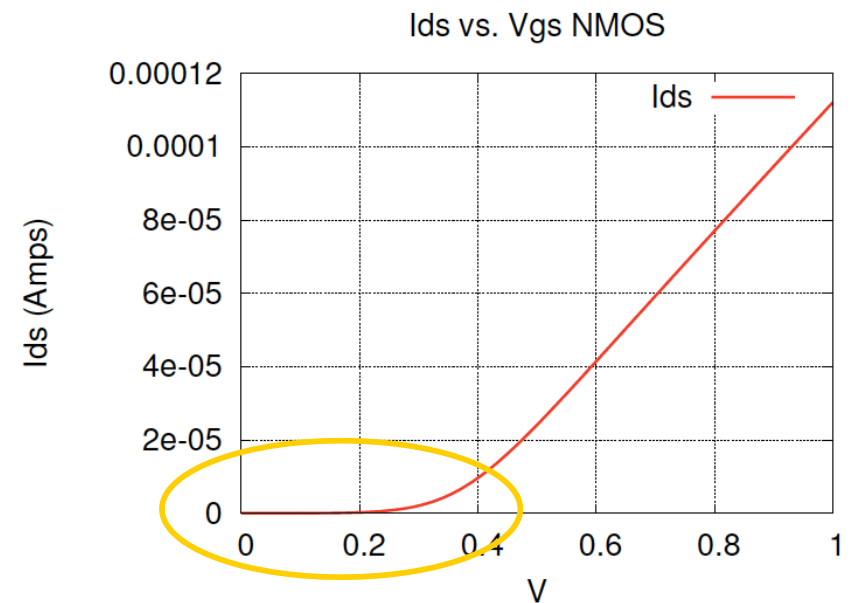
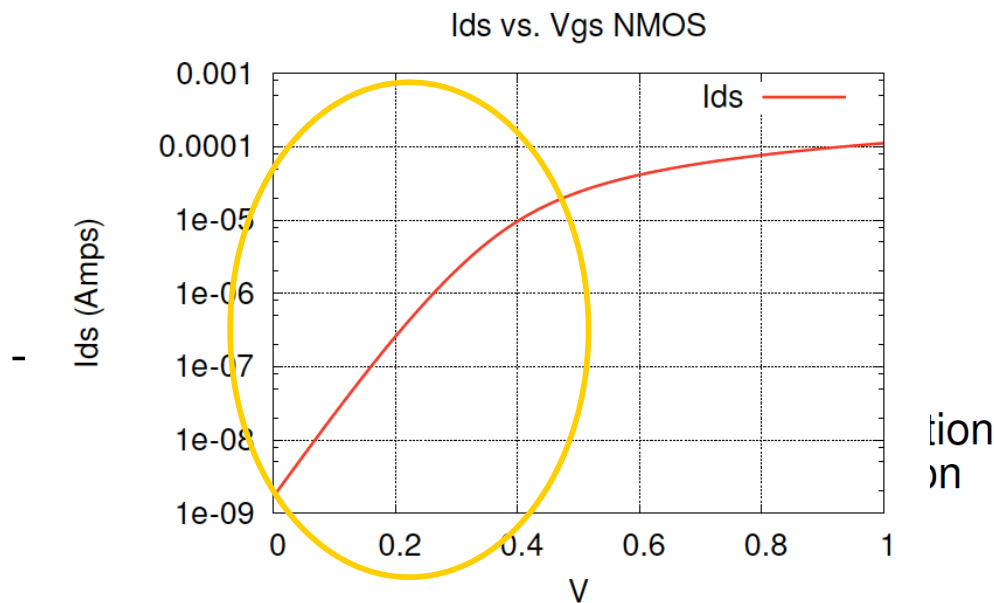
Below Threshold

- ❑ Transition from insulating to conducting is non-linear, but not abrupt
- ❑ Current does flow
 - But exponentially dependent on V_{GS}



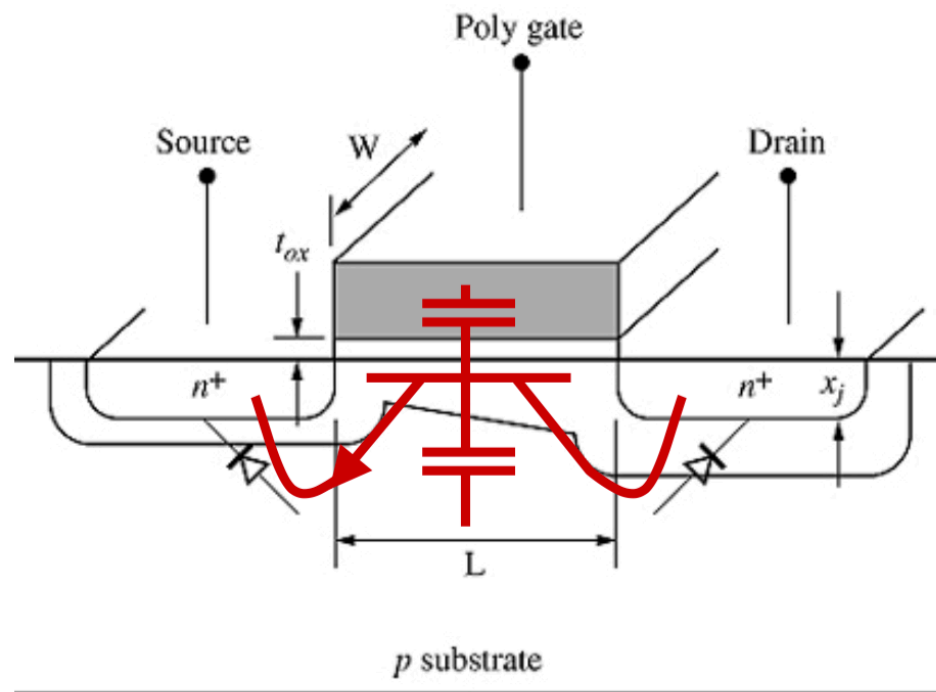
Below Threshold

- ❑ Transition from insulating to conducting is non-linear, but not abrupt
- ❑ Current does flow
 - But exponentially dependent on V_{GS}



Parasitic NPN BJT

- ❑ We have an NPN sandwich, mobile minority carriers in the P region
- ❑ This is a BJT!
 - Except that the base potential is here controlled through a capacitive divider, and not directly an electrode



Subthreshold

If $V_{GS} < V_{th}$,

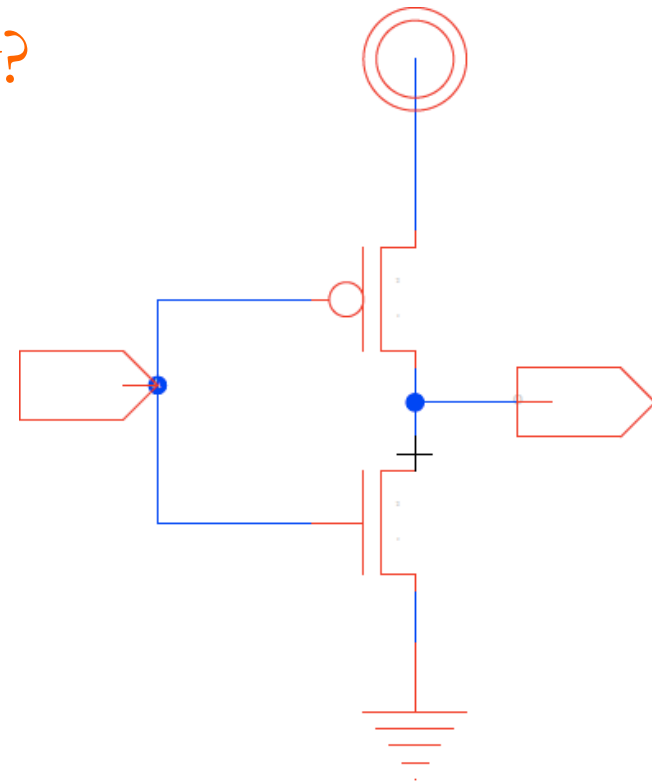
$$I_{DS} = I_S \left(\frac{W}{L} \right) e^{\left(\frac{V_{GS} - V_{th}}{nkT/q} \right)}$$

- Current is from the parasitic NPN BJT transistor when gate is below threshold and there is no conducting channel
 - n is the capacitive divider between parasitic capacitances
 - Typically $1 < n < 1.5$

$$n = \frac{C_{js} + C_{ox}}{C_{ox}}$$

Steady State (Preclass 1)

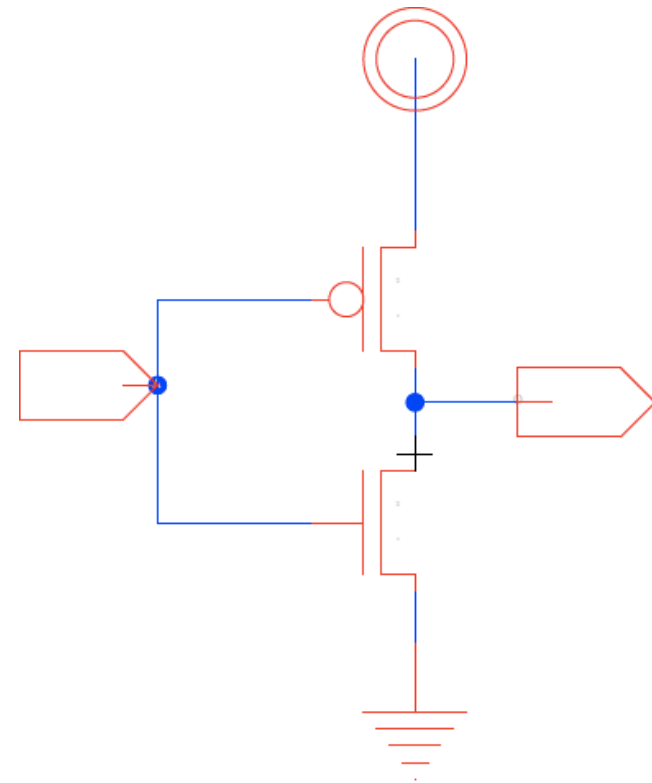
- ❑ What current flows in steady state?
- ❑ What causes (and determines) the magnitude of current flow?
- ❑ Which device?





Leakage

- Call this steady-state current flow leakage
 - $I_{ds,leakage}$

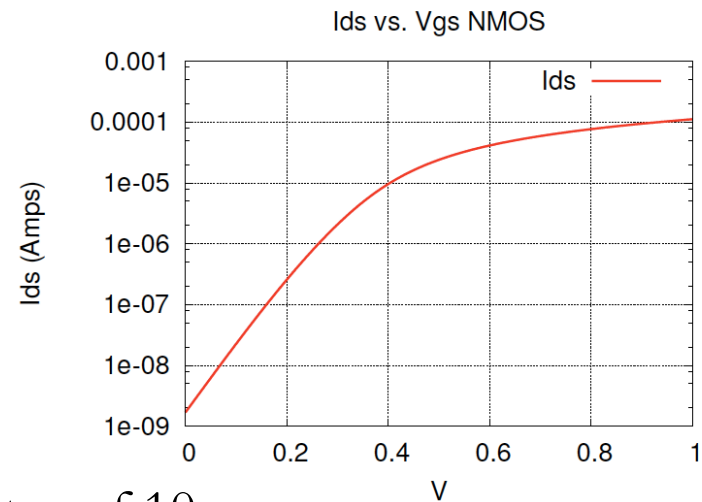


Subthreshold Slope Factor

- Exponent in V_{GS} determines how steep the turnon is

$$S = n \left(\frac{kT}{q} \right) \ln(10)$$

- Units: V/decade
 - Every S Volts, I_{DS} is scaled by factor of 10

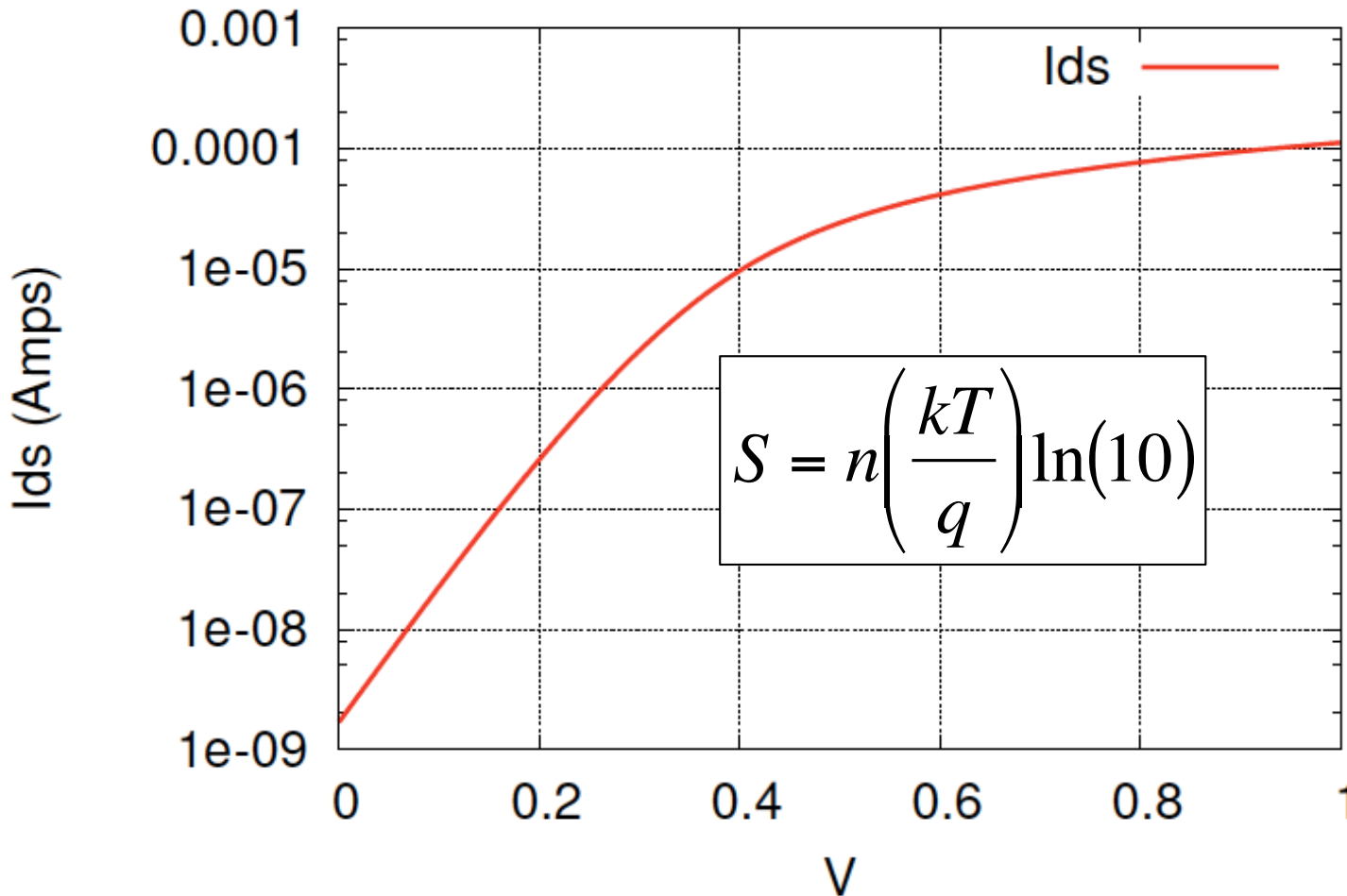


$$I_{DS} = I_S \left(\frac{W}{L} \right) e^{\left(\frac{V_{GS} - V_{th}}{nkT/q} \right)}$$

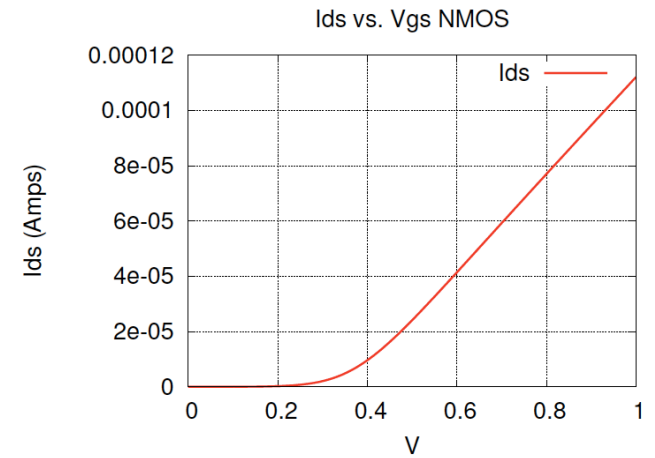


I_{DS} vs. V_{GS}

Ids vs. Vgs NMOS



(Logscale)



Subthreshold Slope Factor

- Exponent in V_{GS} determines how steep the turnon is

$$S = n \left(\frac{kT}{q} \right) \ln(10)$$

- Units: V/dec
- Every S Volts, I_{DS} is scaled by factor of 10
- n – depends on parasitic capacitance divider
 - $n=1 \rightarrow S=60\text{mV}$ at Room Temp. (ideal)
 - $n=1.5 \rightarrow S=90\text{mV}$
 - Single gate structure showing $S=90\text{-}110\text{mV}$

$$n = \frac{C_{js} + C_{ox}}{C_{ox}}$$



Subthreshold Slope Factor (Preclass 2)

- If $S=100\text{mV}$ and $V_{\text{th}}=300\text{mV}$,
what is $I_{\text{ds}}(V_{\text{gs}}=300\text{mV})/I_{\text{ds}}(V_{\text{gs}}=0\text{V})$?

- What if $S=60\text{mV}$?

$$S = n \left(\frac{kT}{q} \right) \ln(10)$$

Velocity Saturation





Carrier Velocity

- Model assumes carrier velocity increases with field
 - Increases with voltage proportionally to mobility

$$v = \mu_n \cdot \frac{V_{DS}}{L_{eff}} = \left(\frac{\mu_n}{L_{eff}} \right) V_{DS}$$

Carrier Velocity

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(3x10⁸ m/sec)





Preclass 3

- (a) What is the electrical field in the channel?

$$L_{eff} = 25nm, V_{DS} = 1V$$

$$\text{Uniform Field} = \frac{V_{DS}}{L_{eff}}$$

- Velocity:

$$v = F \cdot \mu_n$$

- Electron mobility: $\mu_n = 500cm^2 / (V \cdot s)$

- (b) What is the electron velocity?



Moving Charge

$$I = \left(\frac{1}{R}\right)V$$

- ❑ I increases linearly in V
- ❑ What's I?



Moving Charge

$$I = \left(\frac{1}{R}\right)V$$

- I increases linearly in V

- What's I ?
 - $\Delta Q / \Delta t$
 - Speed at which charge moves

Moving Charge

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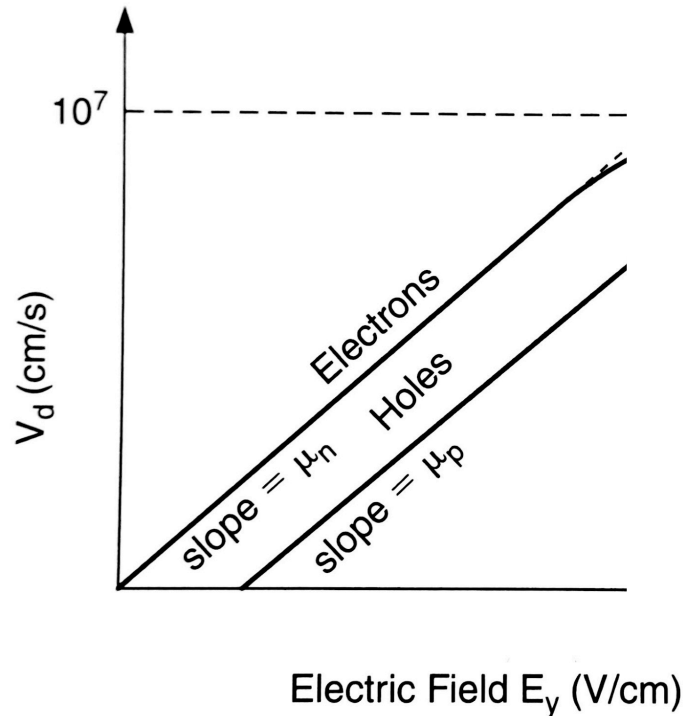
$$Field = \frac{V_{DS}}{L_{eff}}, v = \mu_n \cdot F$$

$$v = \mu_n \cdot \frac{V_{DS}}{L_{eff}} = \left(\frac{\mu_n}{L_{eff}}\right)V_{DS}$$

- Velocity increases linearly in V

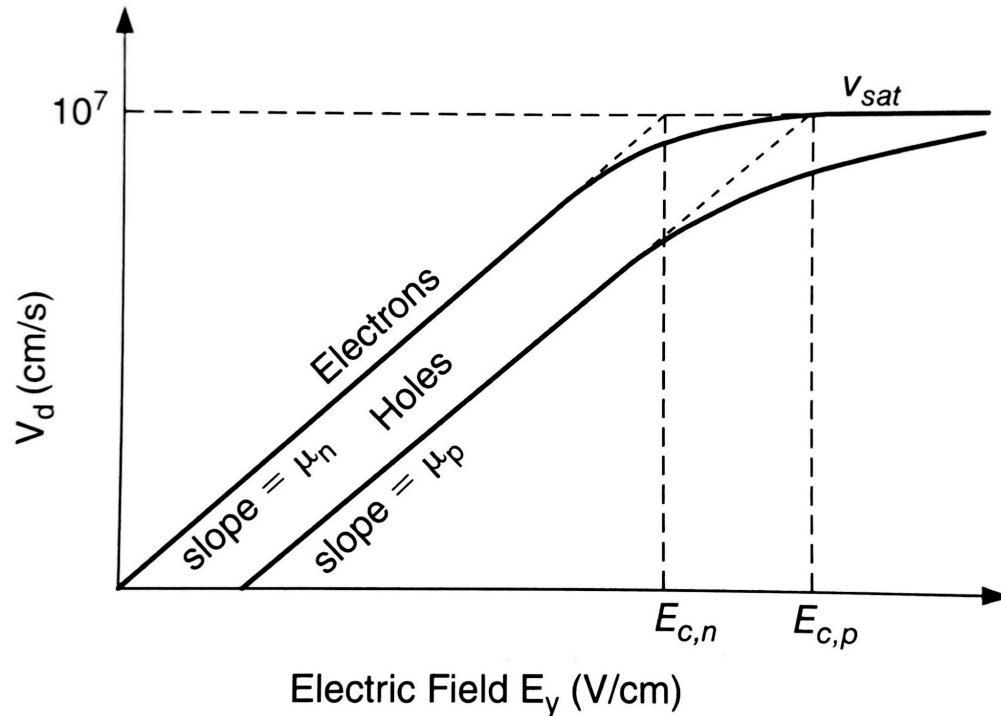
- What's a moving electron?

Carrier Velocity



- Velocity –
 - increases for increasing field with slope of mobility

Carrier Velocity



□ Velocity –

- increases for increasing field with slope of mobility
- saturates for increasing field
 - More likely to hit the critical field in short channel



Short Channel

- ❑ Model assumes carrier velocity increases with field
 - Increases with voltage proportionally to mobility
- ❑ There is a limit to how fast carriers can move
 - Limited by scattering effects
 - $\sim 10^5\text{m/s}$
- ❑ Encounter *velocity saturation* when channel short
 - Modern processes, L is short enough to reach this region of operation



Velocity Saturation (Preclass 3)

- (c) At what voltage do we hit the speed limit 10^5m/s
 - $L_{\text{eff}}=25\text{nm}$, $V_{\text{ds}}=1\text{V}$
 - V_{DSAT} = voltage at which velocity (current) saturates



Velocity Saturation

- Our current model equation:

$$I_{DS} = \mu_n C_{OX} \left(\frac{W}{L} \right) \left[(V_{GS} - V_{th}) V_{DS} - \frac{V_{DS}^2}{2} \right]$$

- Once velocity saturates:



Velocity Saturation

- Our current model equation:

$$I_{DS} = \mu_n C_{OX} \left(\frac{W}{L} \right) \left[(V_{GS} - V_{th}) V_{DS} - \frac{V_{DS}^2}{2} \right]$$

- Once velocity saturates:

$$V_{DS} = V_{DSAT} \Rightarrow I_{DS} = \mu_n C_{OX} \left(\frac{W}{L} \right) \left[(V_{GS} - V_{th}) V_{DSAT} - \frac{V_{DSAT}^2}{2} \right]$$

Velocity Saturation

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$$I_{DS} = \left(\mu_n \frac{V_{DSAT}}{L} \right) C_{OX} W \left[(V_{GS} - V_{th}) - \frac{V_{DSAT}}{2} \right]$$

Velocity Saturation

- Our current model equation:

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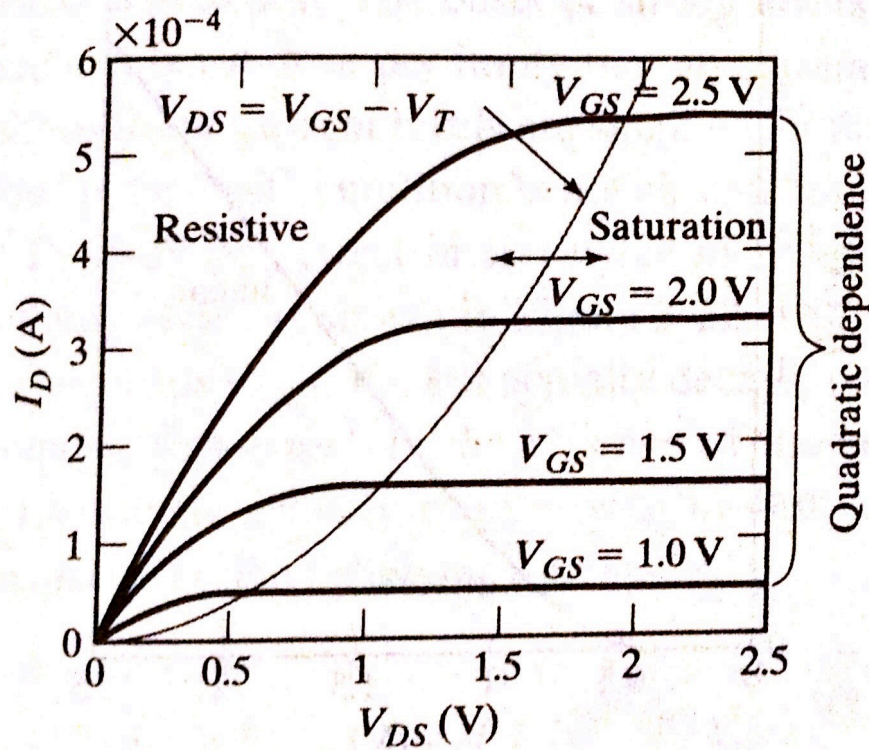
- Once velocity saturates:

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$$I_{DS} = \left(\mu_n \frac{V_{DSAT}}{L} \right) C_{OX} W \left[(V_{GS} - V_{th}) - \frac{V_{DSAT}}{2} \right]$$

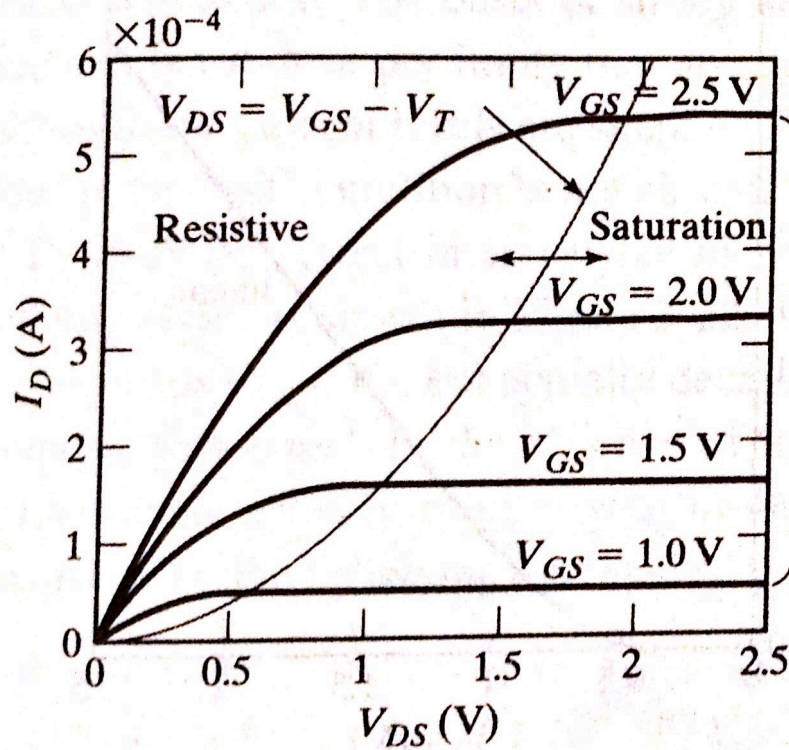
$$I_{DS} \approx v_{sat} C_{OX} W \left[(V_{GS} - V_{th}) - \frac{V_{DSAT}}{2} \right]$$

Velocity Saturation

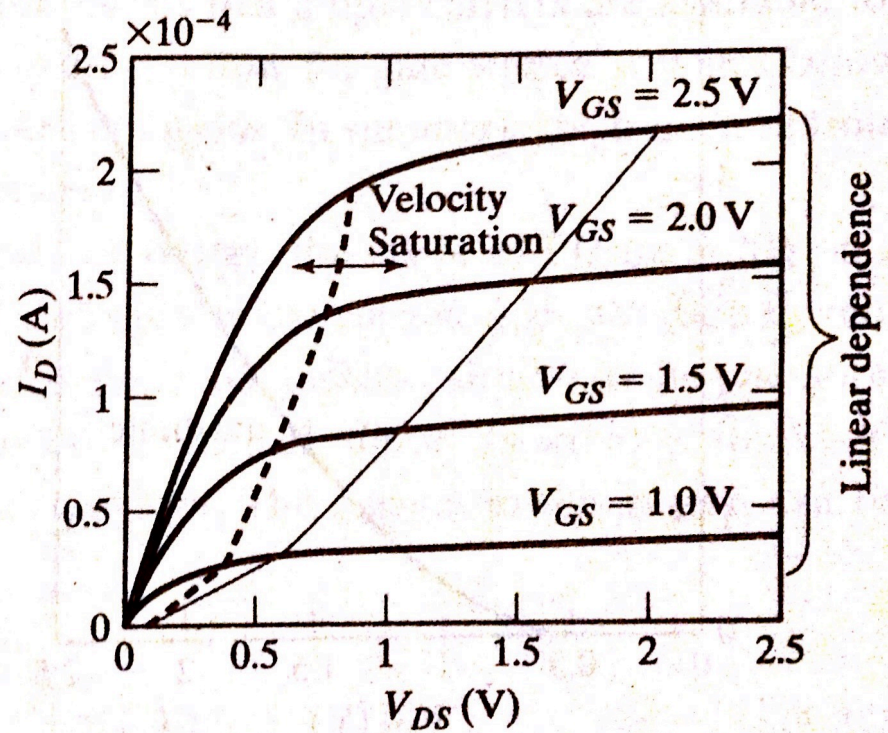


□ Long Channel

Velocity Saturation

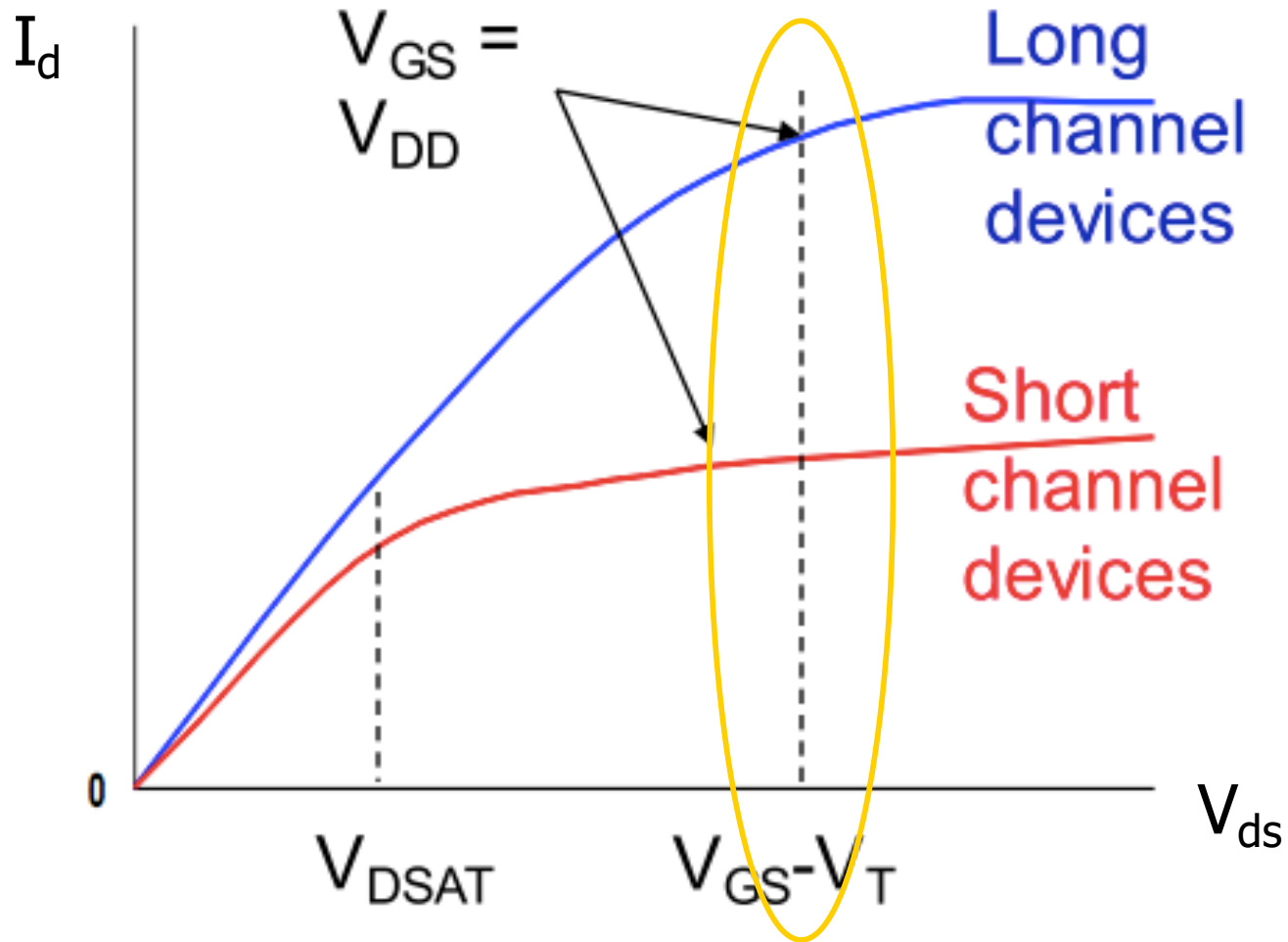


□ Long Channel



□ Short Channel

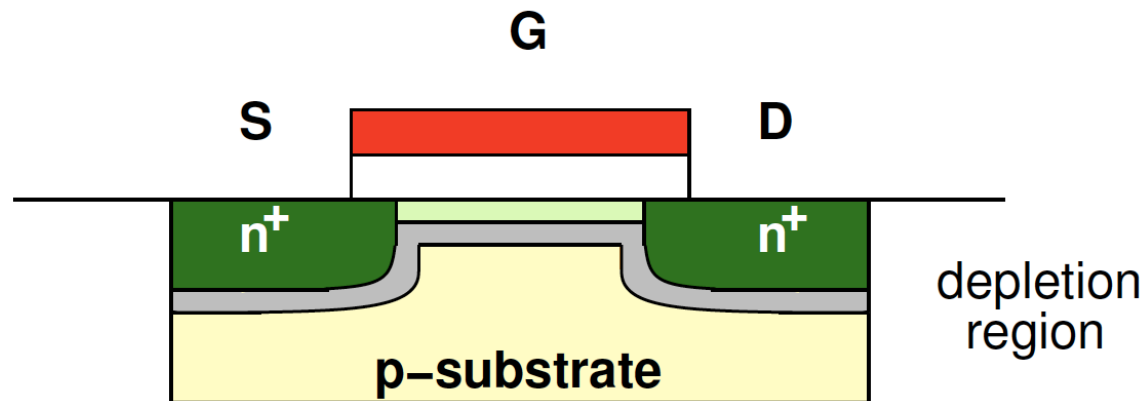
Velocity Saturation



Velocity Saturation

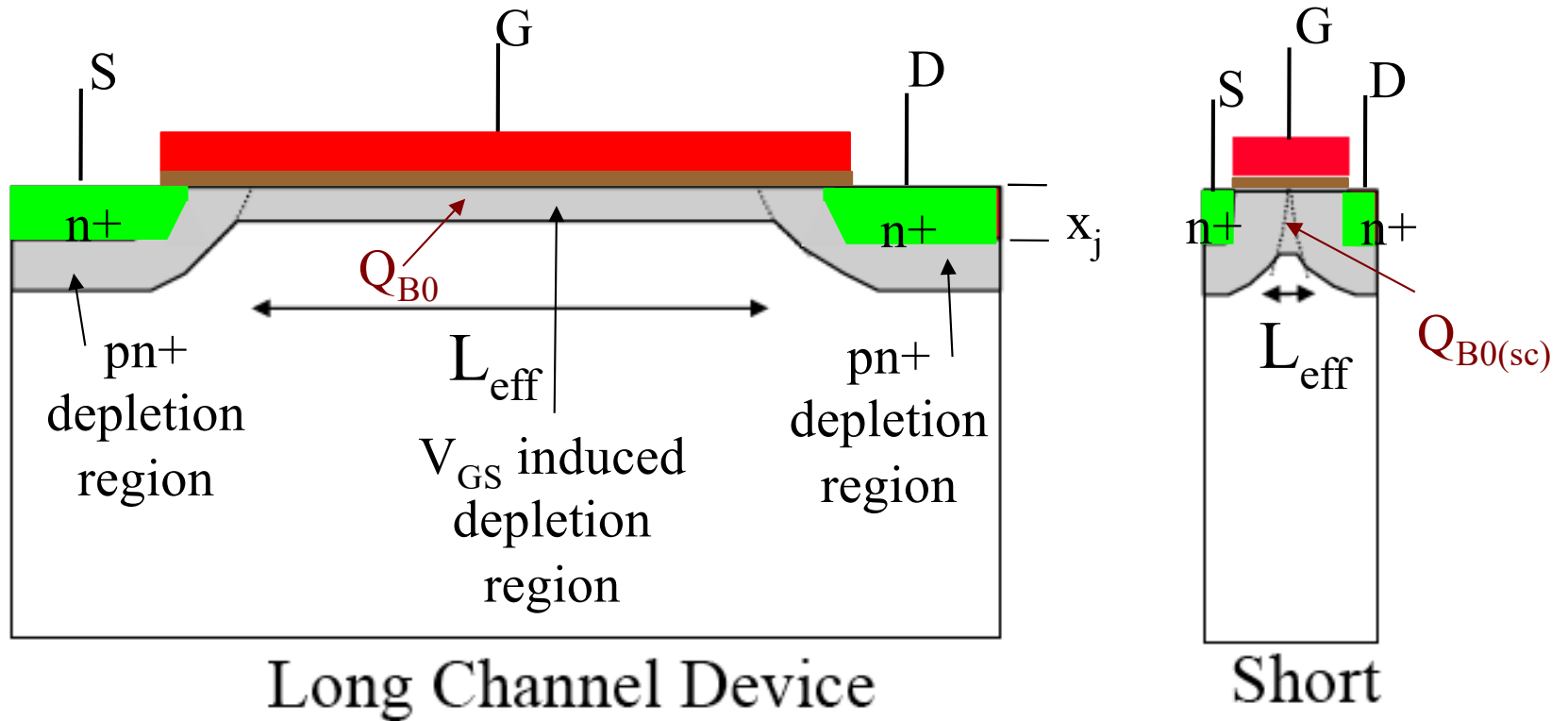
- Once velocity saturates we can still increase current with parallelism
 - Effectively make a wider device

$$I_{DS} \approx v_{sat} C_{OX} W \left[(V_{GS} - V_{th}) - \frac{V_{DSAT}}{2} \right]$$



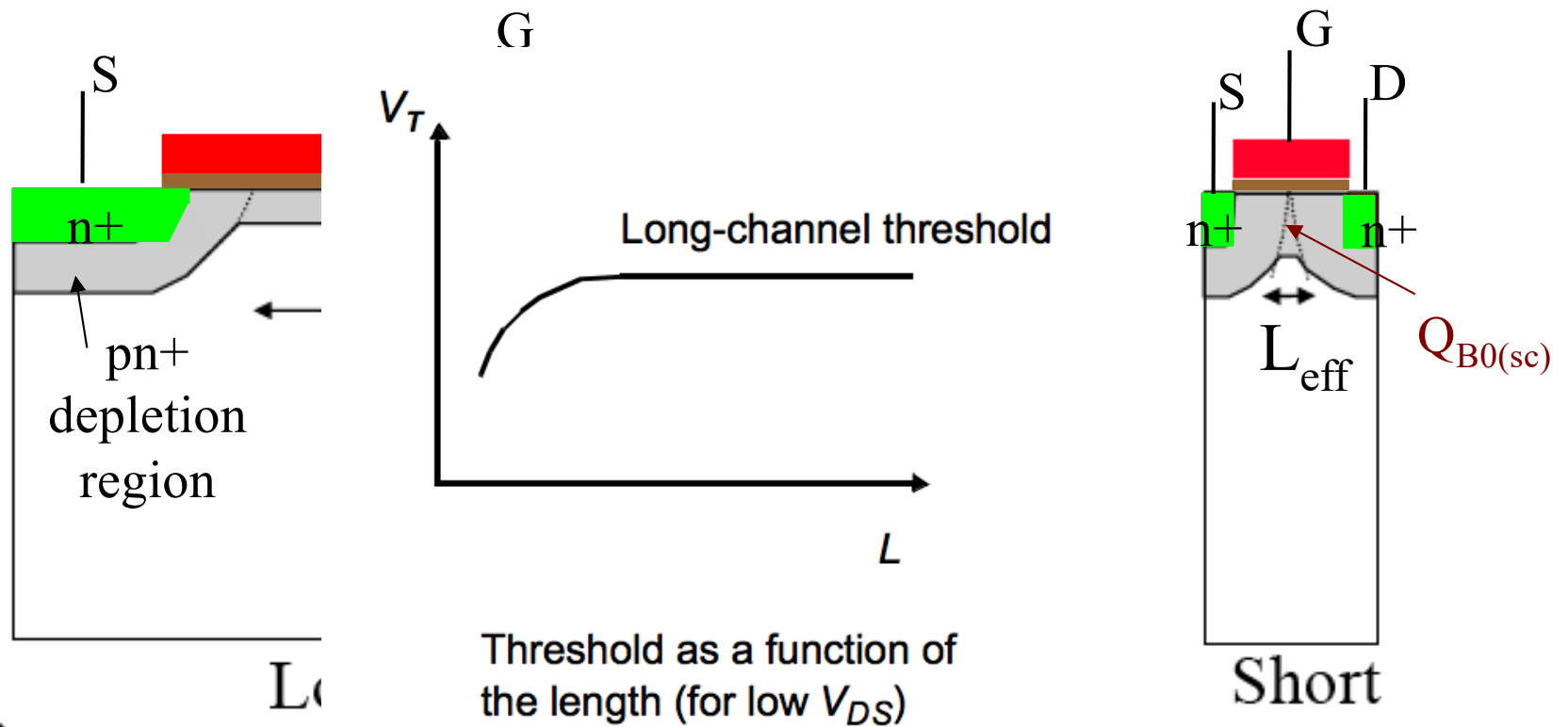
Threshold

Short Channel Effects – V_T Reduction



$$V_{T0} \text{ (short channel)} = V_{T0} - \Delta V_{T0}$$

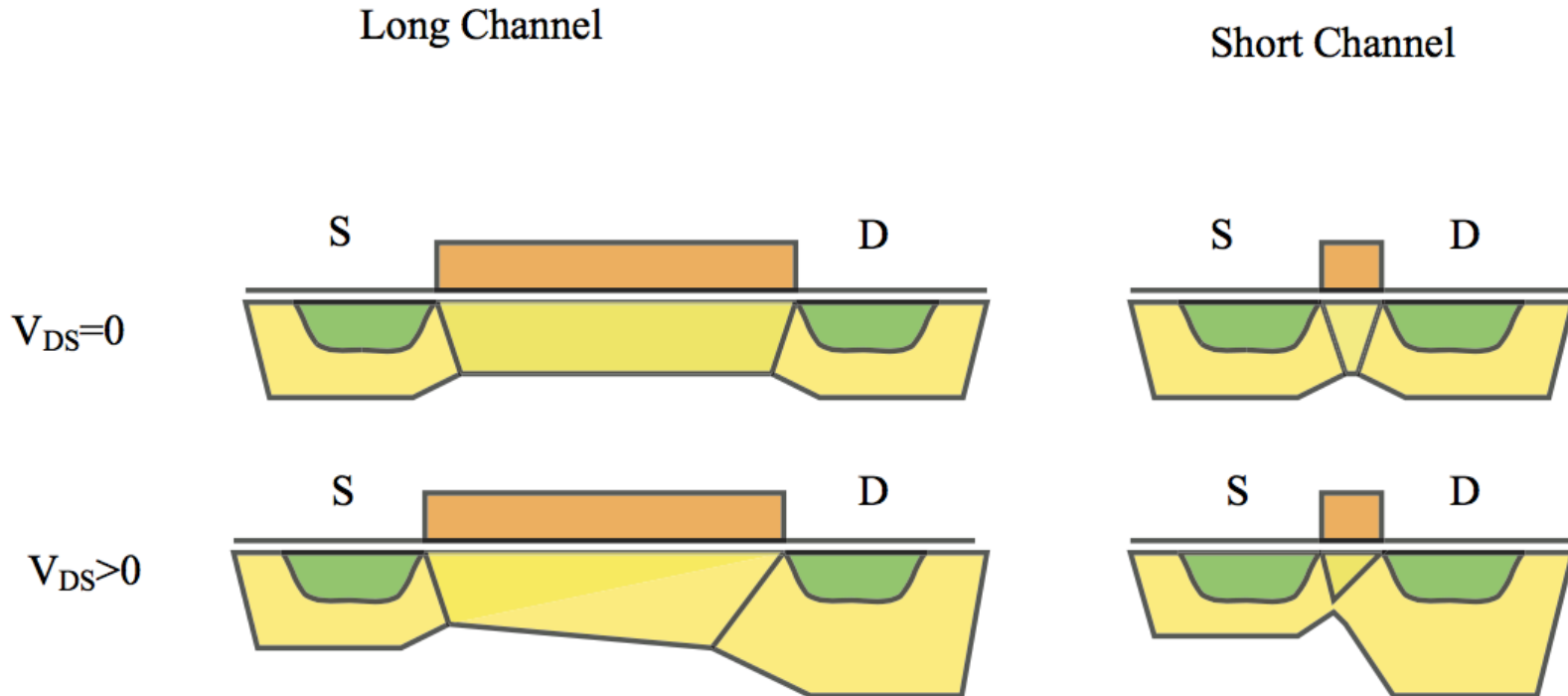
Short Channel Effects – V_T Reduction



$$V_{T0} (\text{short channel}) = V_{T0} - \Delta V_{T0}$$

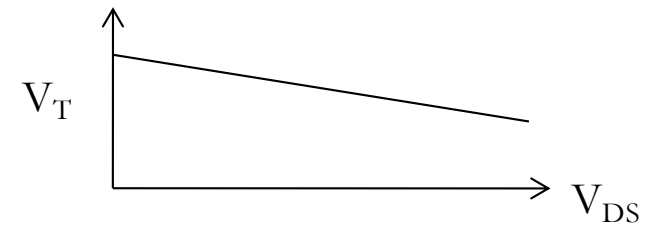
Short Channel Effects - DIBL

- Drain Induced Barrier Lowering
 - V_T Reduction with Drain Bias



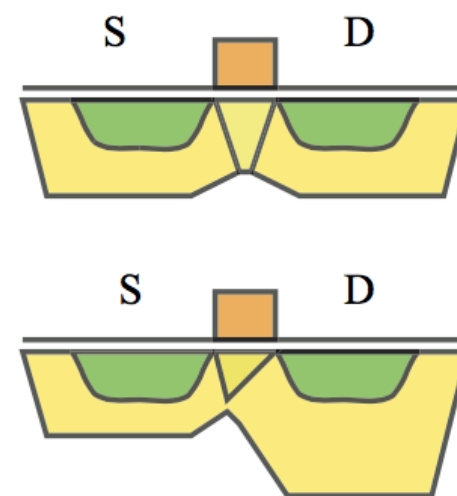
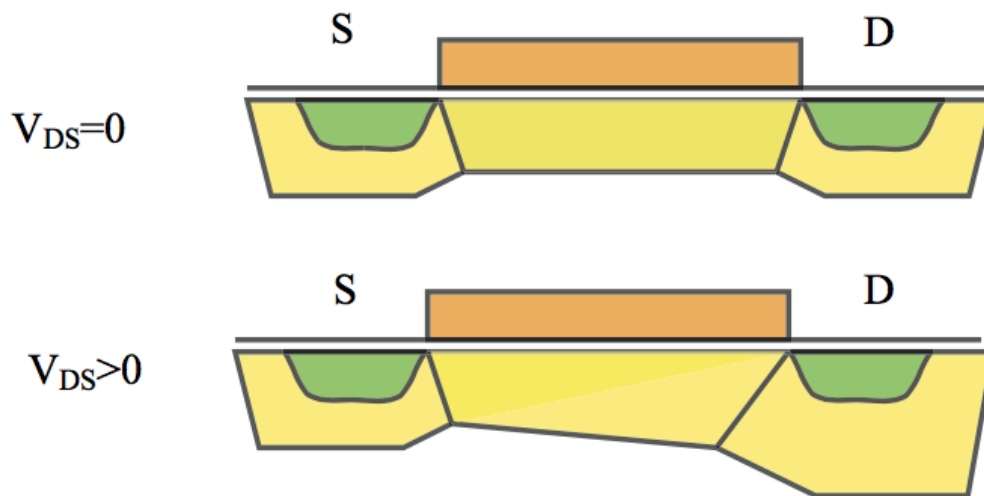
Short Channel Effects - DIBL

- Drain Induced Barrier Lowering
 - V_T Reduction with Drain Bias



Long Channel

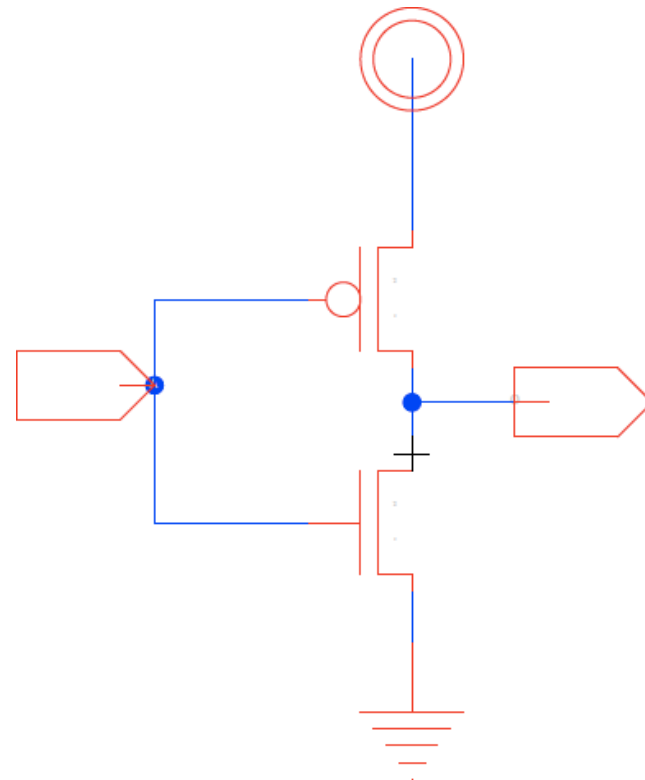
Short Channel



Threshold Reduction Impact

In a Gate?

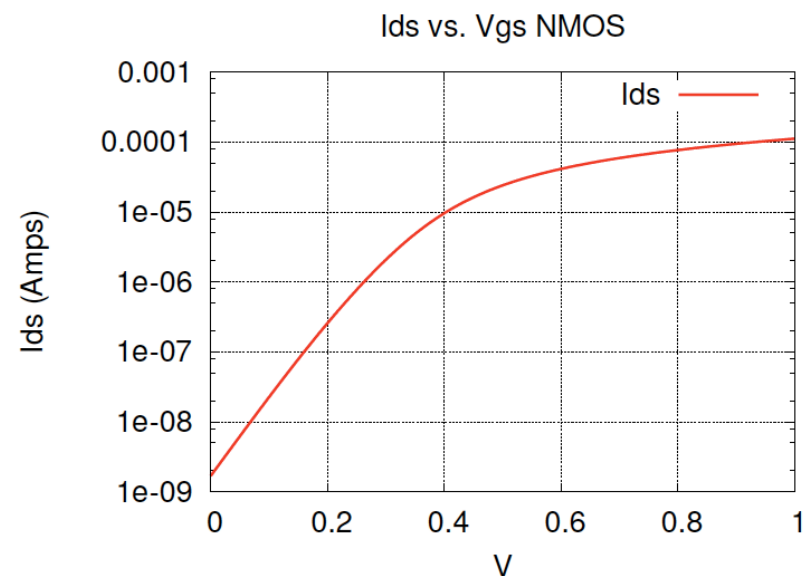
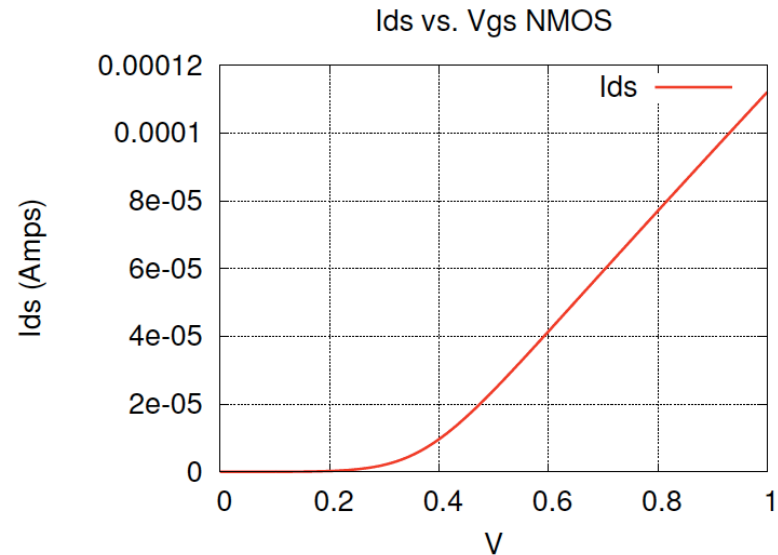
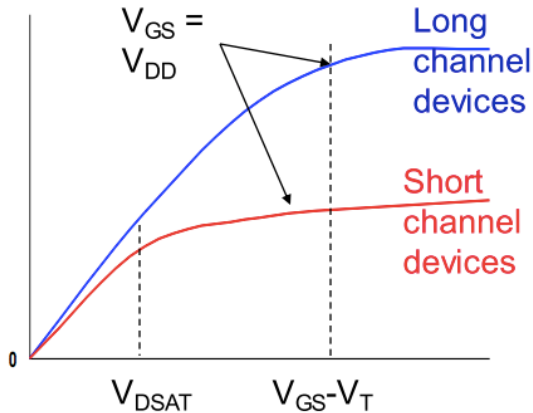
- What does it impact most?
 - Which device, has large V_{ds} ?
 - How does this effect operation?
 - Speed of switching?
 - Leakage?



Big Idea

3+ Regions of operation for MOSFET

- Subthreshold
- Linear
- Saturation
 - Pinch Off
- Velocity Saturation, DIBL
 - Short channel





Admin

- ❑ HW3 due Monday
 - Takes time! Learning curve for how to debug
 - Don't forget the demo/video of SPICE workflow
- ❑ Midterm 1 Review session
- ❑ Midterm 1 Friday 10/1 (next week)
 - 7-9pm in Towne 309
 - No Lecture, virtual office hours
 - (use my OH link on Piazza)
 - Midterms from 2010-2019
 - All online with and without answers
 - Suggest start without answers
 - Conflicts must let me know ASAP